Electronic Supplementary Information (ESI)

Large tunneling magnetoresistance in magnetic tunneling junctions

based on two-dimensional CrX₃ (X=Br, I) monolayers

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Supplementary Figures



Fig. S1. Schematic of a complete device with a pinning layer. The red arrows represent the possible magnetic moment direction of the CrI_3 layers. The left and right parts are Pt electrodes. h-BN monolayer is sandwiched in CrI_3 layers.



Fig. S2. Schematics of (a) $Ag-CrBr_3$; (b) $Au-CrBr_3$; (c) $Al-CrBr_3$; and (d) $Pt-CrI_3$ contacts used in our calculations.



Fig. S3. Schematic of the Brillouin zone of CrI₃-Pt contact. The red frame represents the shape of the true unit cell. The black box represents the Brillouin zone. The symmetry k-points used in the calculation are marked in the figure.